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AMENDMENT TRANSMITTAL LETTER				Docket No. 3273-0196PUS1
Application No. 10/519,998-Conf. #5132	Filing Date January 5, 2005	Examiner J. S. Y. Chu	Art Unit 1752	
Applicant(s): Shigeki KAMBARA et al.				
Invention: PHOTORESIST RESIN AND PHOTORESIST RESIN COMPOSITION				
<b>MS Amendment</b> <b>Commissioner for Patents</b> <b>P.O. Box 1450</b> <b>Alexandria, VA 22313-1450</b>				
Transmitted herewith is an amendment in the above-identified application.				
The fee has been calculated and is transmitted as shown below.				
<b>CLAIMS AS AMENDED</b>				
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate
Total Claims	8	- 20 =		x
Independent Claims	2	- 3 =		x
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>				
Other fee (please specify):				
<b>TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:</b>				0.00
<input checked="" type="checkbox"/> Large Entity <input type="checkbox"/> Small Entity <input checked="" type="checkbox"/> No additional fee is required for this amendment. <input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____. A duplicate copy of this sheet is enclosed. <input type="checkbox"/> A check in the amount of \$ _____ is enclosed. <input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached. <input checked="" type="checkbox"/> The Director is hereby authorized to charge and credit Deposit Account No. <u>02-2448</u> as described below. A duplicate copy of this sheet is enclosed. <input checked="" type="checkbox"/> Credit any overpayment. <input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.				
<u>ny/n-ee # 36,623</u> Dated: <u>May 17, 2006</u> <u>RG</u> <u>Marc S. Weiner</u> Attorney Reg. No.: 32,181				
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Docket No.: 3273-0196PUS1  
(PATENT)

*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

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In re Patent Application of:  
Shigeki KAMBARA, *et al.*

Conf.: 5132

Application No.: January 5, 2005

Art Unit: 1752

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Examiner: John CHU

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For: PHOTORESIST RESIN AND PHOTORESIST  
RESIN COMPOSITION

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**AMENDMENT UNDER 37 CFR 1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

Responsive to the Office Action of February 17, 2006, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This response includes:

Amended Claim Set;

Remarks; and

Joel R. Fried, "Polymer Science & Technology, Second Edition", Prentice Hall, pages 15-17, 128, 129, and 142-145.